

# Ultra-high Q $\text{SiO}_x\text{N}_y$ toroidal microcavities

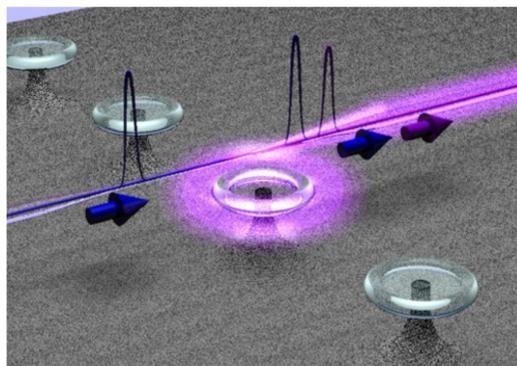
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## Background

Optical microtoroid is an excellent platform for nonlinear optics because light can be confined in the cavity for long time, which makes the optical field inside the cavity strong enough to generate nonlinear behavior.

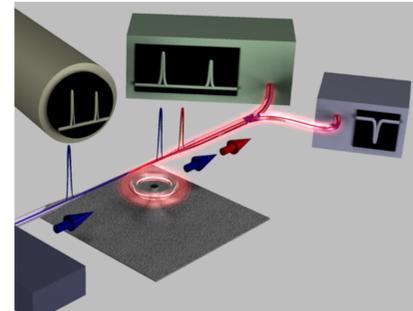
Silicon oxynitride is a promising material for nonlinear research because of its low loss and high nonlinear coefficient. We showed that silicon oxynitride can be used to make microtoroid and tested its Q-factor, which is ultra-high.



Rendering of a microcavity coupled to a tapered optical fiber.

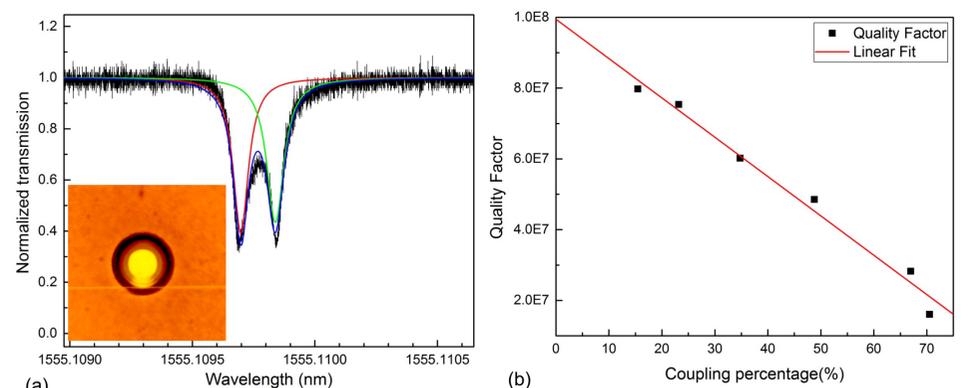
## Data

A standard figure of merit for optical cavities is the quality factor (Q). The Q describes the photon lifetime inside the cavity, and conversely, the optical losses of the cavity. To determine the Q, a tunable laser is scanned across the resonant wavelength, and the transmission spectra is recorded. A tapered optical fiber waveguide is used to couple light into and out of the cavity.



A schematic of the testing set-up showing the laser and oscilloscope. An OSA and a spectrograph are also attached.

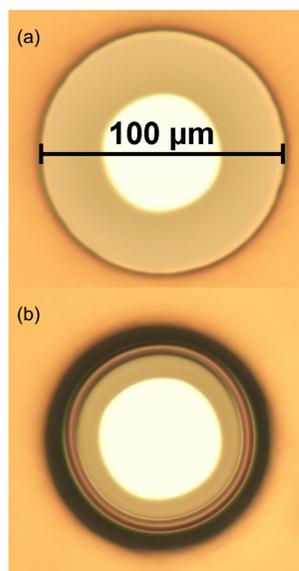
An example transmission spectra taken at 1550nm is shown in the figure below. The resonance exhibited a phenomena known as line-splitting. This occurs when the optical field is coupled into the cavity in both the clock-wise (CW) and counter-clockwise (CCW) directions. In ultra-high-Q cavities, this difference can be detected because the linewidth is extremely narrow. In order to accurately determine the Q of the cavity at a specific coupled power, the peak is fit to a dual-Lorentzian (blue line), and the FWHM of each mode is analyzed separately.



## Fabrication and Testing

The  $\text{SiO}_x\text{N}_y$  wafers were grown at Northrop Grumman. The O:N ratio determines the refractive index of the overall film and governs the chemical resistance of the material, which plays a critical role in the fabrication process. For the initial set of wafers, the oxynitride layer was 1.5 micron thick.

We used a standard microelectronic fabrication method to make  $\text{SiO}_x\text{N}_y$  microtoroid. First, we patterned our wafer with photoresist using photolithography, followed by a series of etching steps to form a  $\text{SiO}_x\text{N}_y$  microdisk on a silicon pillar. Then we use a  $\text{CO}_2$  laser to reflow the microdisk into a toroid structure. The diameter of the microdisk before reflow is 100  $\mu\text{m}$ . After reflow, the diameter of the microtoroid is about 70  $\mu\text{m}$ . The ability to reflow the  $\text{SiO}_x\text{N}_y$  using the  $\text{CO}_2$  laser indicates that the  $\text{SiO}_x\text{N}_y$  has a high absorbance in the mid-IR wavelength range.



Microscope images of (a) microdisk (b) microtoroid

## Discussion & Future Work

We have shown that our devices have Q-factors up to  $10^8$ , which is sufficient to generate multiple nonlinear effects, like Raman laser, frequency combs. Next we would investigate into the nonlinear behavior of our devices, as well as the impact of the O:N ratio. We want to optimize our devices and use them for applications like low threshold Raman lasers, board bandwidth frequency combs.